

**AUXILIARY PATTERN TYPE PHASE SHIFT MASK**

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**International Class (IPC Edition 5):**

- G03F-001/08
- H01L-021/027

**JAPIO Class:**

- 29.1 (PRECISION INSTRUMENTS--- Photography & Cinematography)
- 42.2 (ELECTRONICS--- Solid State Components)

**Abstract:**

**PURPOSE:** To improve the degree of freedom in the arrangement of a main opening by avoiding the situation in which two auxiliary openings of an auxiliary pattern type phase shift mask, that is suitable to form fine contact holes, are partially overlapped to each other and become too large by getting too close to each other.

**CONSTITUTION:** (1) Auxiliary openings 120L, 120T, 120R and 120B, which are placed in the opposite side of a main opening 110 with respect to each other, are arranged so that they are placed at shifted position to each other with respect to the center position of the main opening section. Or, (2) place plural auxiliary openings in a flying granule manner with a prescribed pitch so that the auxiliary opening sections, which are located in the opposite side of the main opening section with respect to each other, are not partially overlapped to each other and not to become too large even though two main openings are getting close to each other. (From: *Patent Abstracts of Japan*, Section: , Section No. FFFFFFFF, Vol. 94, No. 10, Pg. FFFFFFFF, FF, FFFF (FFFFFFFF))

**JAPIO**

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